

WHAT IS CLAIMED IS:

1. A method of making a diamond product by etching, said method comprising the steps of:

5 forming a diamond substrate with a mask layer; and etching said diamond substrate formed with said mask layer with a plasma of a mixed gas composed of a gas containing an oxygen atom and a gas containing a fluorine atom;

10 wherein said fluorine atom has a concentration within the range of 0.04% to 6% with respect to the total number of atoms in said mixed gas.

15 2. A method of making a diamond product according to claim 1, wherein said plasma is produced by generating a high-frequency discharge between two plate electrodes arranged in parallel; and

20 15 wherein said high-frequency discharge is generated by supplying an electric power of at least 0.45 W/cm² between said plate electrodes.

25 3. A method of making a diamond product according to claim 1, wherein said gas containing said fluorine atom is CF₄ gas; and

wherein said CF₄ gas has a concentration within the range of 0.02% to 3% with respect to the total number of molecules in said mixed gas.

4. A method of making a diamond product according to claim 1, wherein said gas containing said oxygen atom is one of O₂, CO₂, and a mixed gas composed of O₂ and CO₂.

5. A diamond product comprising:

a diamond substrate;

formed on said diamond substrate by etching, and arranged
5 according to a predetermined rule; and

a plurality of subsidiary protrusions randomly formed
between said plurality of aligned protrusions upon etching;

wherein said aligned protrusions have a side face with
an angle of inclination of at least 78°; and

10 wherein said subsidiary protrusions have a top part
which is not flat, the number of said subsidiary protrusions
being not greater than 20 per 25 μm^2 .

6. A diamond product comprising:

a diamond substrate having a recess formed by etching;

15 and

a plurality of subsidiary protrusions randomly formed
at a bottom part of said recess upon etching;

wherein said recess has a side face with an angle of
inclination of at least 78°; and

20 wherein said subsidiary protrusions have a top part
which is not flat, the number of said subsidiary protrusions
being not greater than 20 per 25 μm^2 .

7. A diamond product comprising:

a diamond substrate;

25 one protrusion made of diamond and formed on said
diamond substrate by etching; and

a plurality of subsidiary protrusions randomly formed about said one protrusion upon etching;

wherein said one protrusion has a side face with an angle of inclination of at least 78°; and

5 wherein said subsidiary protrusions having a top part which is not flat, the number of said subsidiary protrusions being not greater than 20 per $25 \mu\text{m}^2$.

8. A method of making a diamond product by etching, said method comprising the steps of:

10 forming a diamond substrate with a mask layer; and etching said diamond substrate formed with said mask layer with a plasma of a mixed gas composed of a gas containing an oxygen atom and a gas containing a halogen atom;

15 wherein, in an emission spectrum of said mixed gas, an intensity A of an emission peak caused by said oxygen atom and an intensity B of an emission peak caused by oxygen have an intensity ratio A/B which is greater than the intensity ratio A/B obtained from an emission of a plasma which is 100% oxygen.

20 9. A method of making a diamond product according to claim 8, wherein said gas containing said halogen atom is CF_4 , and wherein said mixed gas further contains nitrogen gas.

25 10. A method of making a diamond product according to claim 8, wherein said emission peak caused by said oxygen atom has a half width of 3 nm or less, and wherein said emission

peak caused by oxygen has a half width greater than 3 nm.